

What is claimed is:

1. A metal-to-metal antifuse formed over a lower Cu metal layer

planarized with the top surface of a lower insulating layer comprising:

a lower barrier layer disposed over the lower Cu metal layer;

- 5 an antifuse material layer disposed over said lower barrier layer;

An upper barrier layer disposed over said antifuse material layer;

an upper insulating layer disposed over said upper barrier layer;

an upper Cu metal layer planarized with a top surface of the upper
insulating layer and having a contact extending therethrough to make electrical

- 10 contact with said upper barrier layer.

2. The metal-to-metal antifuse of claim 1 further including:

a first cap layer disposed over said lower Cu metal layer and the top

surface of said lower insulating layer, said first cap layer having a first-cap-layer

- 15 via formed therethrough exposing a top surface of said lower Cu metal layer,

wherein said lower barrier layer is disposed in said first-cap-layer via in electrical

contact with said lower Cu metal layer; and

a second cap layer enveloping said antifuse material layer and said upper barrier layer said second cap layer having a second-cap-layer via formed therethrough exposing a top surface of said upper barrier layer, wherein said upper Cu metal layer is disposed in said second-cap-layer via.

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3. The metal-to-metal antifuse of claim 1 wherein said antifuse material layer comprises a layer of amorphous silicon.

4. The metal-to-metal antifuse of claim 1 wherein said lower barrier layer comprises a layer of TaN.

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5. The metal-to-metal antifuse of claim 1 wherein said upper barrier layer comprises a layer of TiN.

6. The metal-to-metal antifuse of claim 2 wherein said first and second cap layers are formed from TiN.

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7. The metal-to-metal antifuse of claim 2 wherein said antifuse material layer comprises a layer of amorphous silicon.

8. The metal-to-metal antifuse of claim 2 wherein said lower barrier layer comprises a layer of TaN.

9. The metal-to-metal antifuse of claim 2 wherein said upper barrier layer comprises a layer of TiN.

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10. A method for fabricating a metal-to-metal antifuse comprising:
forming a lower barrier layer over a lower Cu metal layer planarized with the top surface of a lower insulating layer;

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forming an antifuse material layer over said lower barrier layer;
forming An upper barrier layer over the antifuse material layer;
defining said antifuse layer and said upper barrier layer;
forming an upper insulating layer over said upper barrier layer and said antifuse layer;

forming a via in said upper insulating layer to expose a top surface
of said upper barrier layer;

forming an upper Cu metal layer over said upper insulating layer and
in said via to make electrical contact with said upper barrier layer; and

5 planarizing a top surface of said upper Cu metal layer and a top
surface of said upper insulating layer.